MEO Engineering Company, Inc.

High Tech on Small Scale Since 2004

GALEX™ Instruments FIB/SEM Deposition Precursor Gas Injector

DESIGN HIGHLIGHTS

- Easy installation, alignment, and start-up
- Compatible with deposition precursors
- User-exchangeable and re-loadable cartridges, self-service precursor exchange
- Port-mounted and always ready, no lengthy preparations prior to operation
- Most precursors ready for injection within seconds after sample pump-down
- Rapid switch, no internal absorption for most precursors, no lengthy degassing
- Injection of multiple gases without position correction or re-alignment
- Desktop or rack-mountable controller, push-button operation or computerized **GUI** control
- Self-sealed precursor cartridges improve handling and safety compliance
- Double-sealed shipping containers comply with safety regulations
- Fail-safe normally-closed process valves for safe power-loss shutdown
- Fail-safe retraction facilitates withdrawal in case of air pressure loss or power shutdown
- Customization for experimental precursors and application development support available
- Designed and built by people with decades of expertise in FIB instrumentation, gas injection and FIB GAE
- Gas Assisted Etching version is available
- UHV-compatible version upon request

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PRECURSOR HANDLING

Number of cartridges: 3 - standard, 4- upon request Precursor cartridge housing: Heated and room temperature -

standard

Cooled - optional

Gas switch time: 10 Sec for chemically compatible

precursors

Heated cartridge temperature: Ambient to +65°C Cooled cartridge temperature: Ambient to +10°C

Precursor cartridge capacity: 2.0 cm³

Precursor cartridge design: Self-sealed, re-loadable and user-

replaceable

Wetted materials (standard): Al (Ni plated), Ni (plated on Al),

SST-304, Viton (FKM), PBT, Ultra

Chemically Resistant PVC.

Standard wetted materials are compatible with most typical deposition and etching precursors: Pt, W, Mo, C, SiOx, XeF2. Substitutions of wetted materials for other chemistries available upon request.



Patent Pending

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INJECTOR MOUNTING

Weight: 1.6 kG (3.4 lb)

Mounting: Tool-specific adapter

with Viton O-Ring

Insertion/Retraction stroke: 22mm Insertion/Retraction time: < 5 Sec Needle insertion repeatability: $\pm 5 \mu m$

SHIPPING CONTAINER

Dimensions: 22" x 18" x 11"

(56cm x 46cm x 28cm)

Weight: 30lb (15kg)

CONTROLLER

Configurable 1U desktop or 19" rack-mountable with push-button interface and GUI through USB PC interface.

UTILITIES

Vacuum: 10E-2 Torr or better by system or

dedicated rough pump.

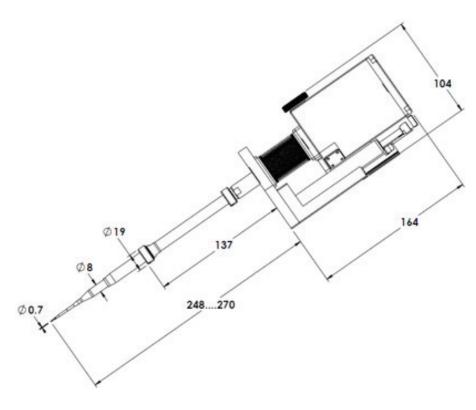
 DN_2 , CDA, or compressed air: 90PSI \pm 15PSI stand-alone or

integrated IN/OUT control

Purge gas (N₂, O₂, Ar) optional: 5PSI ± 1PSI

Computer interface: USB

DIMENSIONAL SKETCH (mm)



Patent Pending

CONTACT US FOR YOUR NEXT PROJECT

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